

ABSTRACT

A photomask blank to be used as a material for a
5 photomask is provided with a mask pattern having a
transparent area and an effectively opaque area to exposure
light on a transparent substrate. On the transparent board,
one or more layers of light shielding films are formed with
or without other film (A) in between, at least one layer (B)
10 which constitutes the light shielding film includes silicon
and a transition metal as main component, and a molar ratio
of silicon to the transition metal is silicon:metal = 4-15:1
(atomic ratio). The photomask provided with the mask pattern
having the transparent area and the effectively opaque area
15 to exposure light on the transparent board is also provided.